

ON-CHIP INTEGRATION OF A μ MUX AND MMB DETECTOR FOR QUBIC COLLABORATION

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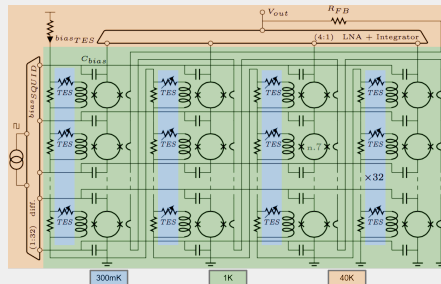
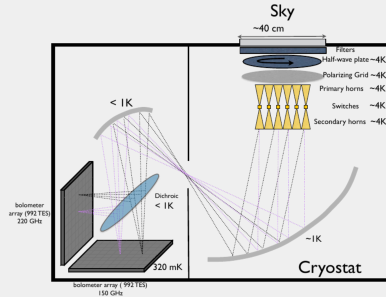
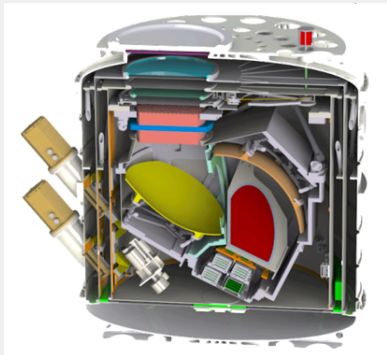
- Background: QUBIC
- Superconductor microwave resonators
- Tri-layer tests
- Preliminary results
- Future work



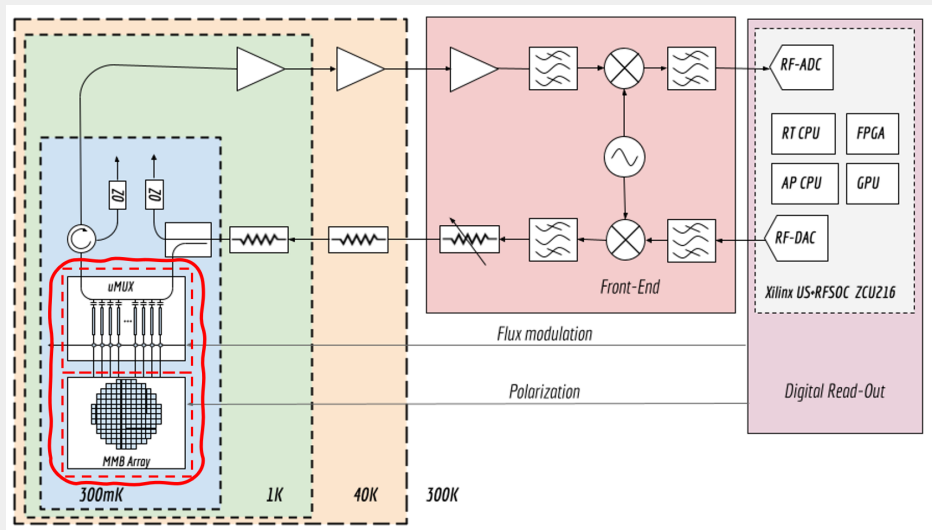
- (QUBIC: Q&U Bolometric Interferometer for Cosmology)
- Cosmology experiment: CMB (B-Modes).
- Proposal for the Focal Plane (ARG-GER).

October 2022: QUBIC deployed in Salta, Argentina, at the mountain site (4869 m a.s.l.)

QUBIC INSTRUMENT

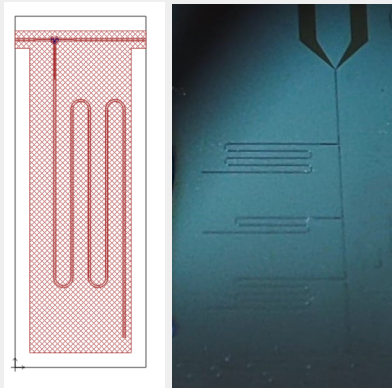


QUBIC INSTRUMENT: FOCAL PLANE SECOND VERSION



My thesis work is focused on show the possibilities to combine the μ mux SQUID Multiplexer with the MMB Detectors.*

SUPERCONDUCTOR MICROWAVE RESONATORS (SMR)



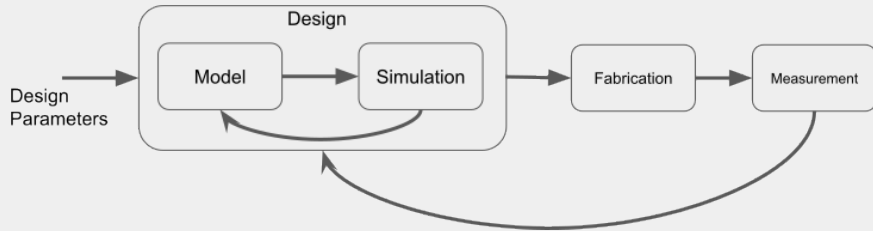
First steps in optimisation of the superconductor microwave resonators

Quarter wave resonator:

Coplanar waveguide resonators

Frequency ranges: 4 to 8 GHz

Bandwidth: 200 kHz



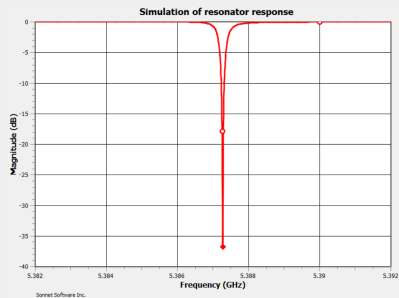
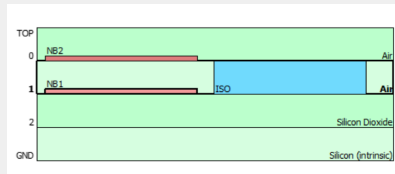
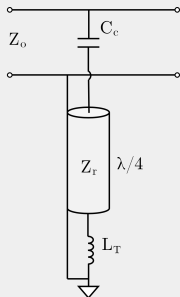
Development tools for resonators design.

Superconductor materials: Niobium, Aluminum.

Substrate materials: Silicon, Silicon dioxide.

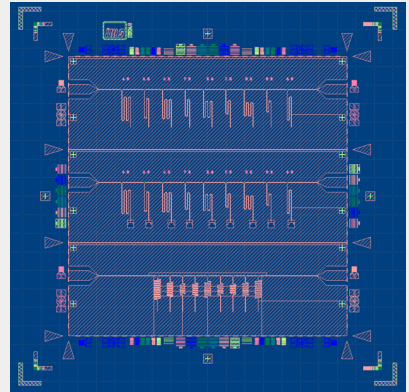
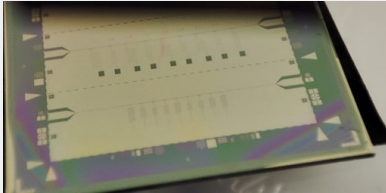
Resonance frequency:

$$f_r' = \frac{f_r}{1 + 4f_r C_c Z_r + 4f_r L_{(\Phi)} / Z_r}$$



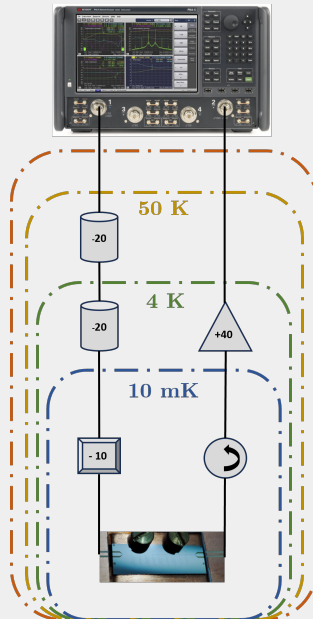
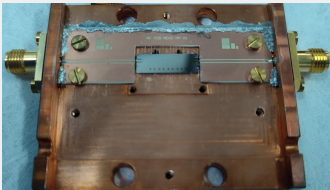
Niobium resonators fabrication at IMS (GER)
by Eng. Nahuel Müller.

- 9 bare resonators
- Resonators with L_T
- Another geometry with different C_c .



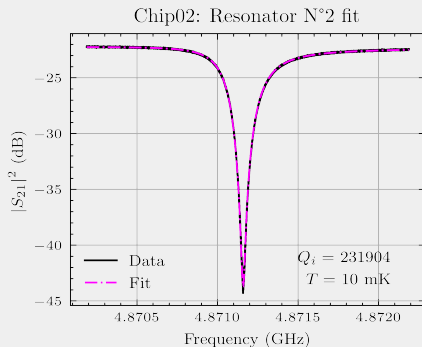
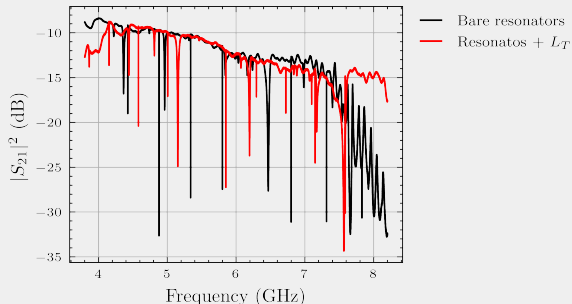
RF Setup for low temperature measurements (ARG).

- Bluefors LD250.
 - ▶ Channel 1 ≈ 45 dB nominal attenuation
LNA: LNF4_8C (3301H)
 - ▶ Channel 2 ≈ 55 dB nominal attenuation
LNA: LNF4_8C (3464H)
- N5242B PNA-X Microwave Network Analyzer.

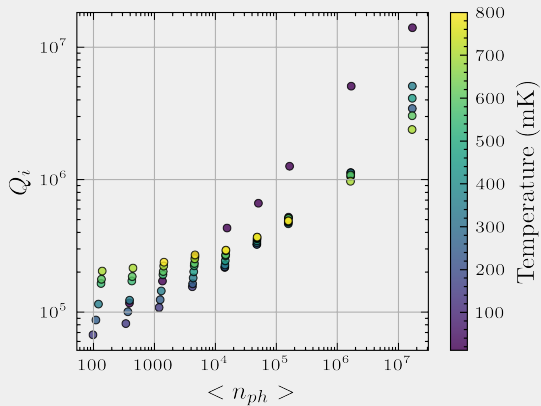
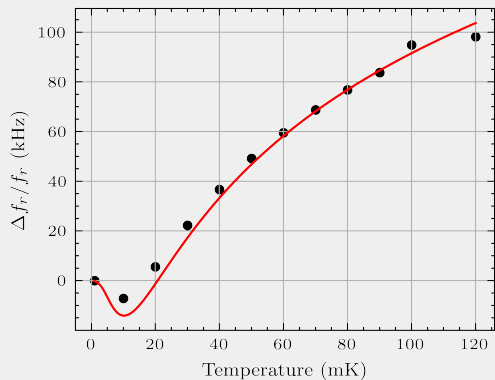


9 resonators design from 4 to 8 GHz

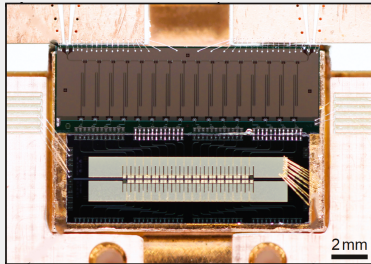
- Chip 01: Bare resonators.
- Chip 02: Resonators + L_T .



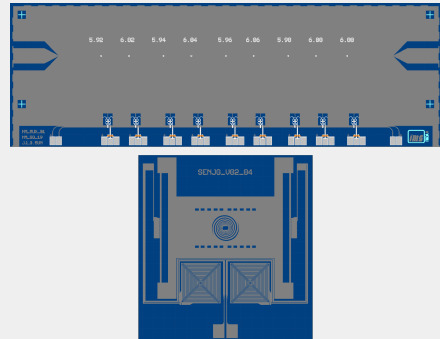
$$S_{21}(f) = ae^{i\alpha} e^{-2\pi if\tau} \left[1 - \frac{(Q_l/|Q_c|)e^{i\phi}}{1 + 2iQ_l(f/f_r - 1)} \right]$$



- Match between different fabrication process
- Higher thickness in the first Nb layer.
- High I_c for Detector coil.



D. Richter (2021)

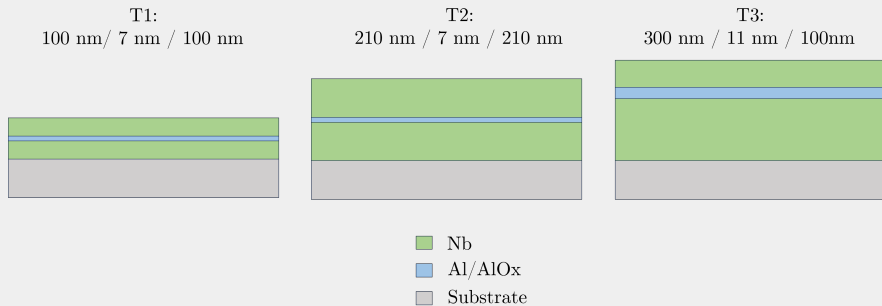


Eng. Nahuel Müller and Eng. Juan Geria

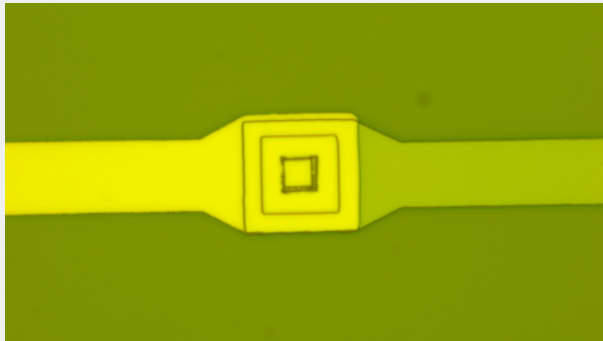
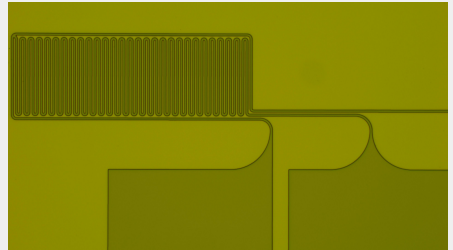
Description of the fabrication process currently used for umux development at IMS.
Tri-layer deposition (Nb: 100 nm / Al/AlOx: 7 nm / Nb: 100 nm).

#	Name	Material	Thickness (nm)	Process
1	Bottom layer	Nb	100	Sputtering + dry etching
2	Tunnel barrier	Al - AlOx	7	Sputtering + wet etching
3	Top layer	Nb	100	Sputtering + dry etching
4	First isolation layer	SiO ₂	125	Sputtering + lift-off
5	Second isolation layer	SiO ₂	125	Sputtering + lift-off
6	Last connection layer	Nb	300	Sputtering + lift-off

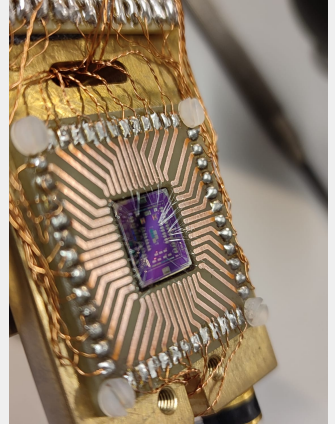
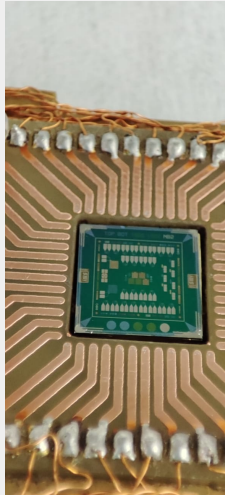
ONGOING WORK: TRI-LAYER TESTS



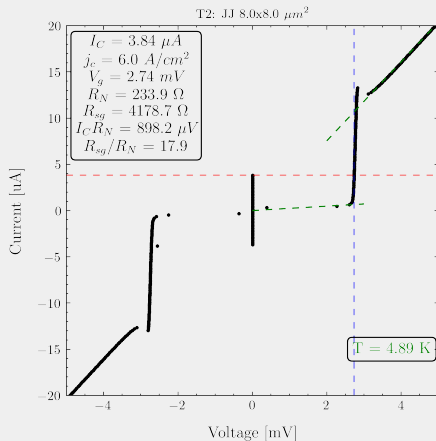
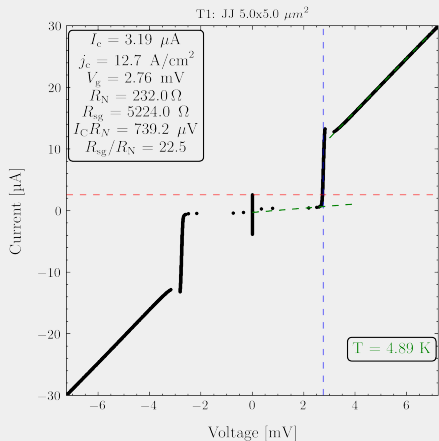
Functionality of the Josephson Junctions with a thicker Bottom layer of Nb.



ONGOING WORK: CRYOGENIC MEASUREMENTS



Preliminary results.



Gracias, Thanks, Danke :)

BACK UP

